

	Hits	Search Text	DBs
6	3	355/67.ccls. and ((illuminat\$4 or expos\$4 or irradiat\$4) same ((beam near9 split\$4) or mirror) same (pluralit\$4 or multiple or two or three)) and ((mask or reticle or (pattern\$4 near9 structure) or (pattern\$5 near22 element) or (pattern\$4 near18 means)) same angle same (adjust\$4 or chang\$4 or var\$6)) and ((substrate or wafer) near14 (support or hold\$4 or stage)) and (((spatial near14 modulat\$4) or (pluralit\$4 near (mask or pixel))) same pattern\$4 same array)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
7	2	355/77.ccls. and ((illuminat\$4 or expos\$4 or irradiat\$4) same ((beam near9 split\$4) or mirror) same (pluralit\$4 or multiple or two or three)) and ((mask or reticle or (pattern\$4 near9 structure) or (pattern\$5 near22 element) or (pattern\$4 near18 means)) same angle same (adjust\$4 or chang\$4 or var\$6)) and ((substrate or wafer) near14 (support or hold\$4 or stage)) and (((spatial near14 modulat\$4) or (pluralit\$4 near (mask or pixel))) same pattern\$4 same array)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
8	0	430/5.ccls. and ((illuminat\$4 or expos\$4 or irradiat\$4) same ((beam near9 split\$4) or mirror) same (pluralit\$4 or multiple or two or three)) and ((mask or reticle or (pattern\$4 near9 structure) or (pattern\$5 near22 element) or (pattern\$4 near18 means)) same angle same (adjust\$4 or chang\$4 or var\$6)) and ((substrate or wafer) near14 (support or hold\$4 or stage)) and (((spatial near14 modulat\$4) or (pluralit\$4 near (mask or pixel))) same pattern\$4 same array)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
9	0	((illuminat\$4 or expos\$4 or irradiat\$4) same ((beam near9 split\$4) or mirror) same (pluralit\$4 or multiple or two or three)) and ((mask or reticle or (pattern\$4 near9 structure) or (pattern\$5 near22 element) or (pattern\$4 near18 means)) same angle same (adjust\$4 or chang\$4 or var\$6) same pupil same ((numerical near9 aperture) or NA)) and ((substrate or wafer) near14 (support or hold\$4 or stage)) and (((spatial near14 modulat\$4) or (pluralit\$4 near (mask or pixel))) same pattern\$4 same array)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
10	0	((mask or reticle or (pattern\$4 near9 structure) or (pattern\$5 near22 element) or (pattern\$4 near18 means)) same angle same (adjust\$4 or chang\$4 or var\$6) same pupil same ((numerical near9 aperture) or NA)) and ((substrate or wafer) near14 (support or hold\$4 or stage)) and (((spatial near14 modulat\$4) or (pluralit\$4 near (mask or pixel))) same pattern\$4 same array)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
11	0	((mask or reticle or (pattern\$4 near9 structure) or (pattern\$5 near22 element) or (pattern\$4 near18 means)) same angle same (adjust\$4 or chang\$4 or var\$6) same pupil same ((numerical near9 aperture) or NA)) and ((substrate or wafer) near14 (support or hold\$4 or stage)) and (((spatial near14 modulat\$4) or (pluralit\$4 near16 (mask or pixel))) same pattern\$4 same array)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
12	1	((mask or reticle or (pattern\$4 near9 structure) or (pattern\$5 near22 element) or (pattern\$4 near18 means)) same angle same (adjust\$4 or chang\$4 or var\$6) same (multiple or pluralit\$9) same (pupil near9 plane) same ((numerical near9 aperture) or NA)) and ((substrate or wafer) near14 (support or hold\$4 or stage))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
13	23	((mask or reticle or (pattern\$4 near9 structure) or (pattern\$5 near22 element) or (pattern\$4 near18 means)) same angle same (adjust\$4 or chang\$4 or var\$6) same pupil same ((numerical near9 aperture) or NA)) and ((substrate or wafer) near14 (support or hold\$4 or stage))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
14	0	((mask or reticle or (pattern\$4 near9 structure) or (pattern\$5 near22 element) or (pattern\$4 near18 means)) same angle same (adjust\$4 or chang\$4 or var\$6) same pupil same ((numerical near9 aperture) or NA)) and ((substrate or wafer) near14 (support or hold\$4 or stage)) and ((SLM or (pattern\$9 near16 array) or (pattern\$4 near18 plural\$5) or (position\$4 near12 arrang\$5)) same (expos\$4 or irradiat\$4 or illuminat\$4 or beam\$3) same angle same ((NA or (numerical near9 aperture)) near16 (high\$5 or larg\$3 or big\$4)))	US-PGPUB

	Hits	Search Text	DBs
15	0	((mask or reticle or (pattern\$4 near9 structure) or (pattern\$5 near22 element) or (pattern\$4 near18 means)) same angle same (adjust\$4 or chang\$4 or var\$6) same pupil same ((numerical near9 aperture) or NA)) and ((substrate or wafer) near14 (support or hold\$4 or stage)) and ((SLM or (pattern\$9 near16 array) or (pattern\$4 near18 plural\$5 near22 array) or (position\$4 near12 arrang\$5)) same (expos\$4 or irradiat\$4 or illuminat\$4 or beam\$3) same angle same ((NA or (numerical near9 aperture)) near16 (high\$5 or larg\$3 or big\$4)))	US-PPGPUB